

## ABSTRACT OF THE DISCLOSURE

5        Provided herein is a method of improving the  
planarity of a support plate of a susceptor for use during  
deposition of a film of material onto a substrate comprising the  
steps of reducing pressure in a hollow core of a shaft to a level  
below atmospheric pressure; and reducing a pressure in the  
deposition chamber to a level required for the deposition of the  
10    film of material onto the substrate, where the pressure in the  
hollow core of the shaft acts upon a lower surface of the support  
plate connected to the shaft and interfacing with the hollow core  
of the shaft and the pressure in the deposition chamber acts upon  
an upper surface of the support plate adapted to support the  
15    substrate thereby improving planarity. Also provided are a  
susceptor and a method of depositing a film onto a substrate  
affixed to the susceptor of the present invention.